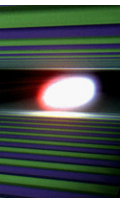


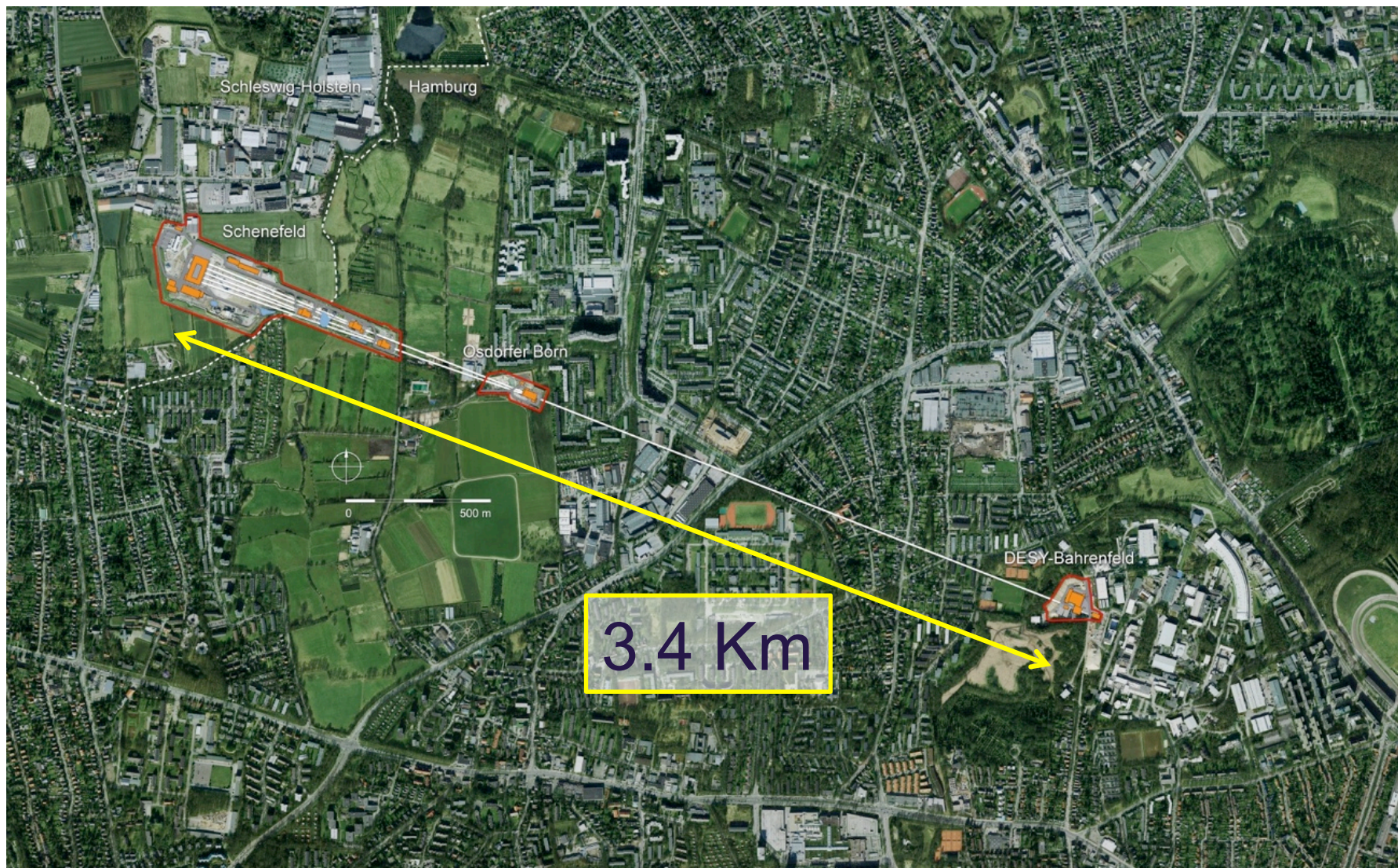
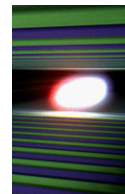
The European XFEL deformable optics project

Maurizio Vannoni
(European XFEL GmbH)

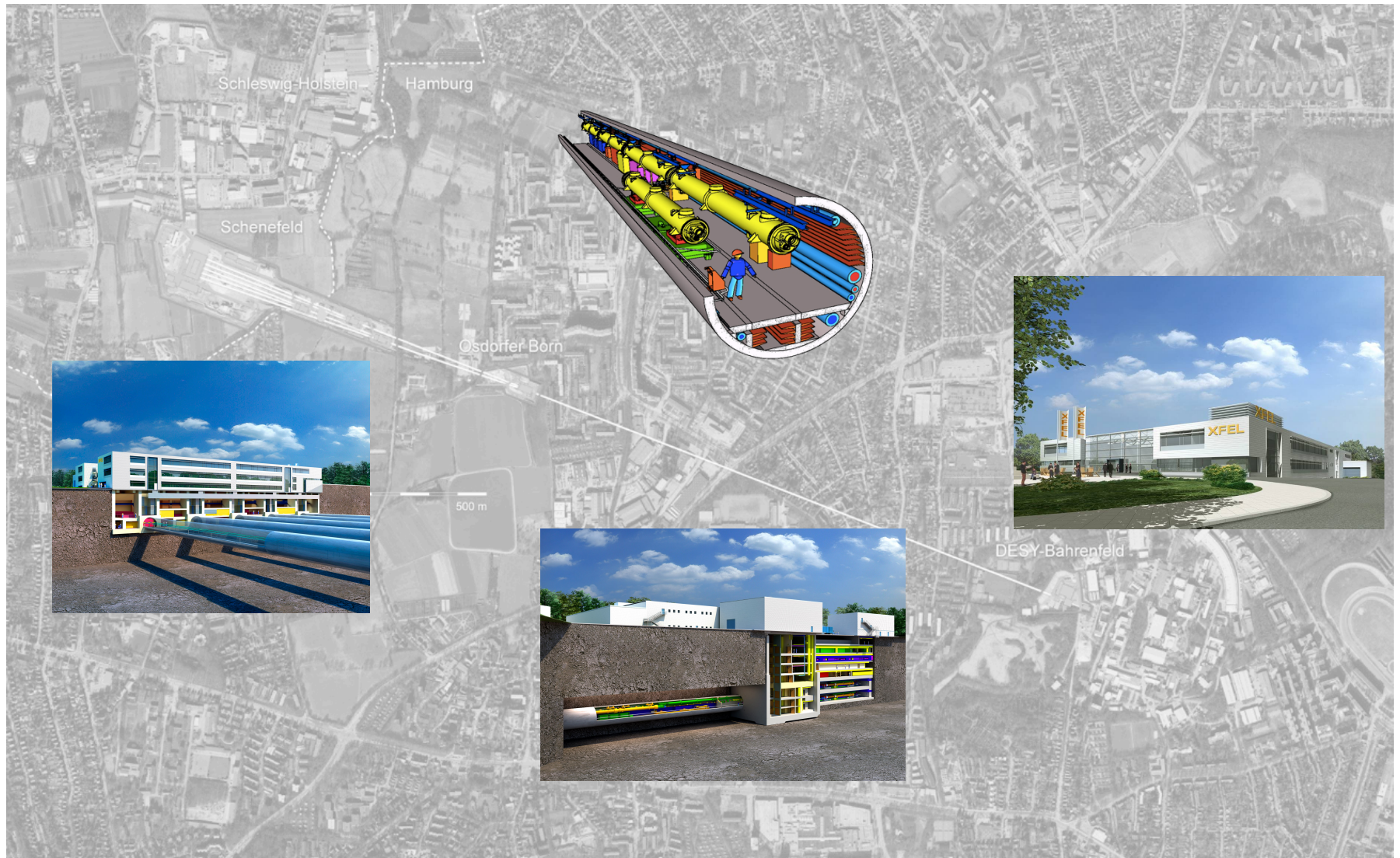
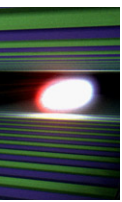


- Overview of the European XFEL project
- Bendable Mirrors in the Distribution System
- General Specifications
- Metrology
- Status of the project and future plans

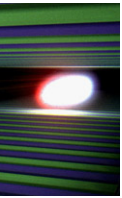
Overview of the European XFEL project



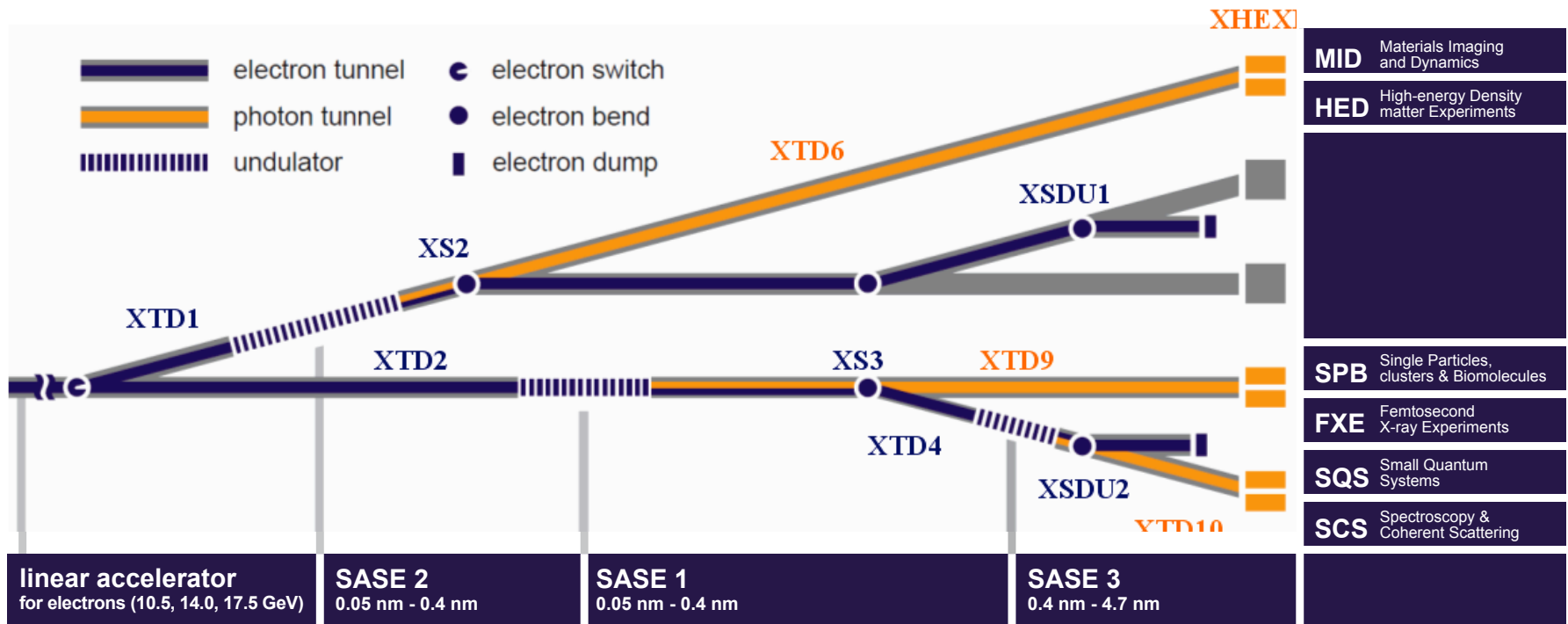
Overview of the European XFEL project



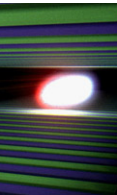
Overview of the European XFEL project



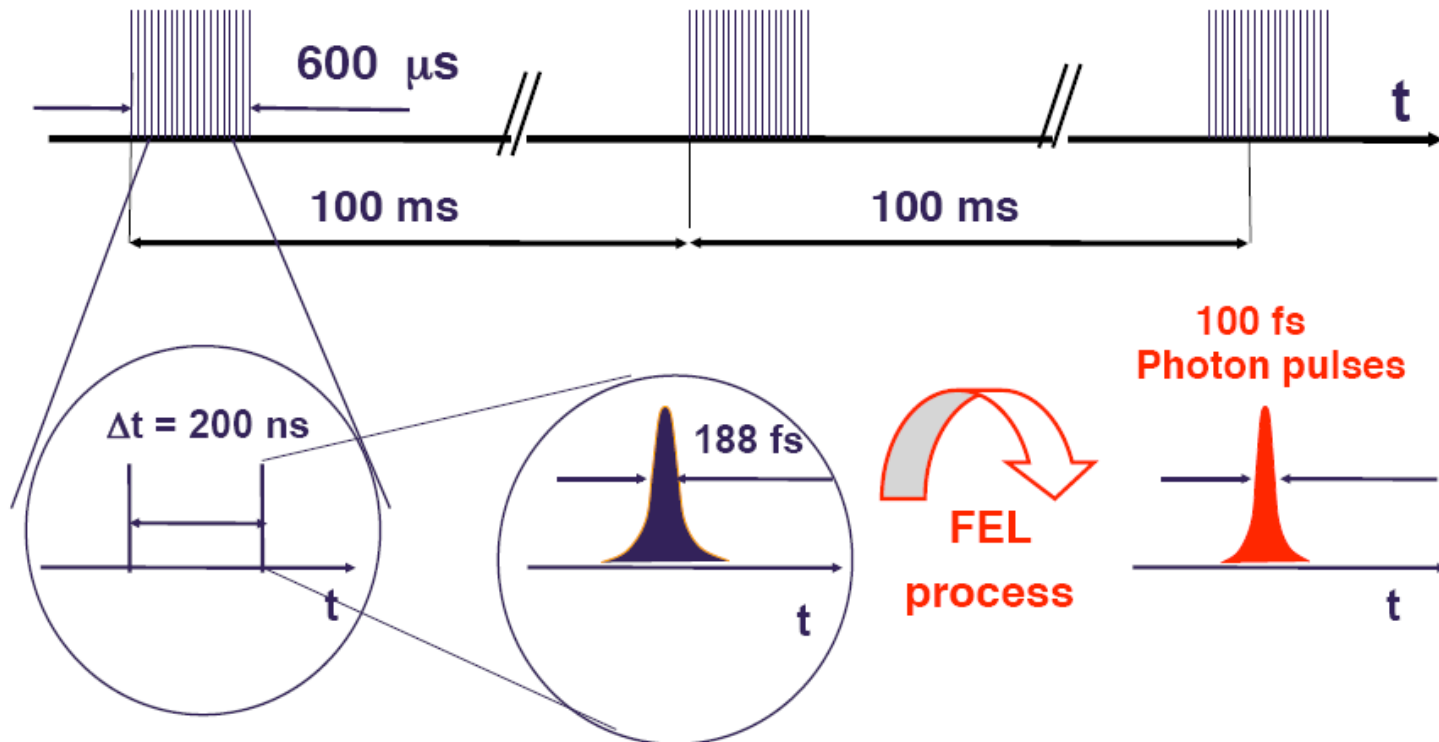
Undulator Segment	FEL radiation energy [keV]	Wavelength [nm]
SASE 1	3 - over 24	0.4 - 0.05
SASE 2	3 - over 24	0.4 - 0.05
SASE 3	0.27 - 3	4.7 - 0.4



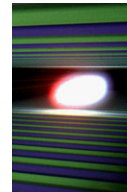
Overview of the European XFEL project



Up to 27000 pulses every second
(2700 pulses / 10 Hz)



Thermal effect on offset mirror



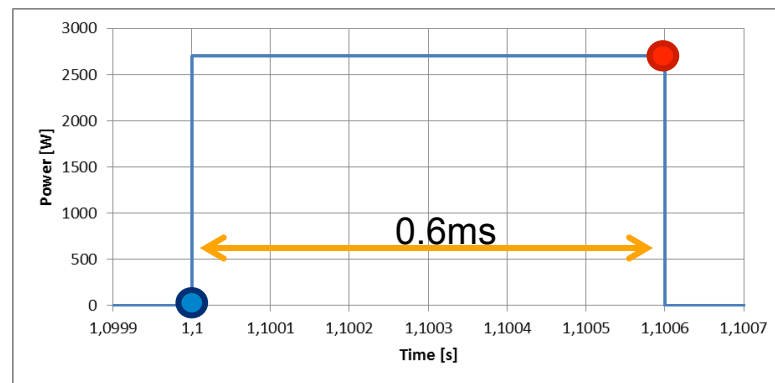
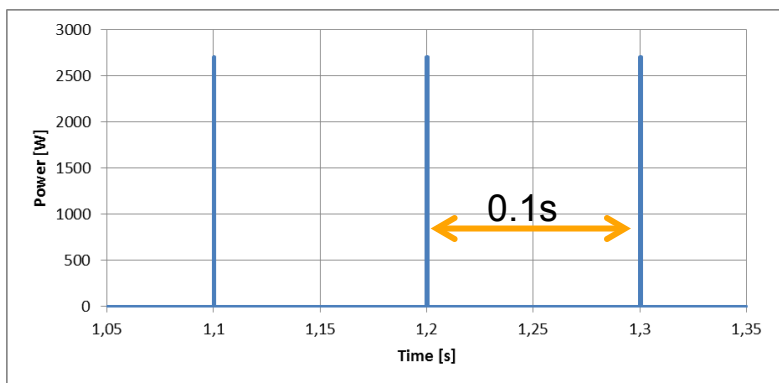
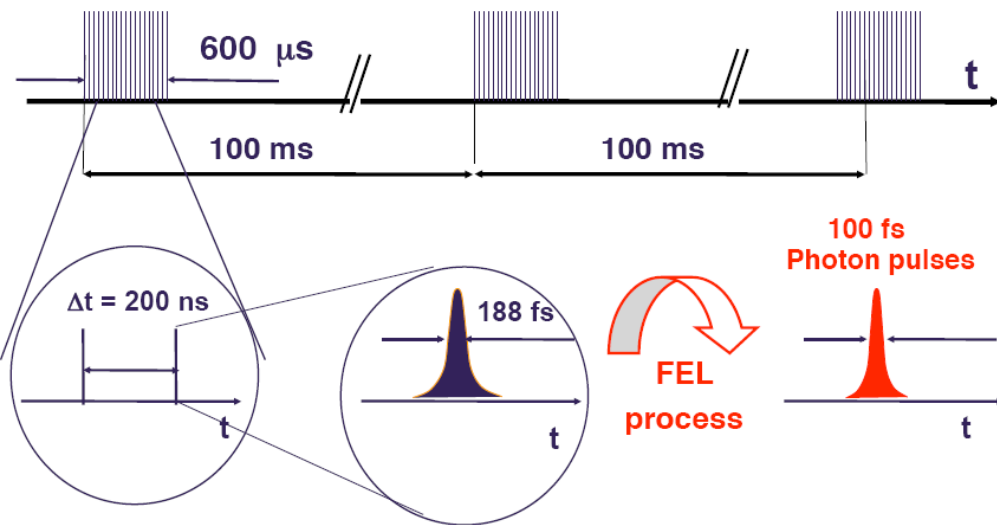
M. Altarelli et al., The XFEL Technical Design Report, 2006

Pulse time structure:

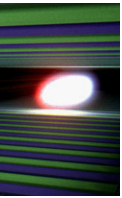
- # pulses / train = 2700
- Pulse train duration = 0,6ms
- Pulse train rep. rate = 10Hz

Assuming 10mJ as pulse energy:

- $P_{\text{pulse}} = 100\text{GW}$
- $P_{\text{train}} = 45\text{kW}$
- $P = 270\text{W}$

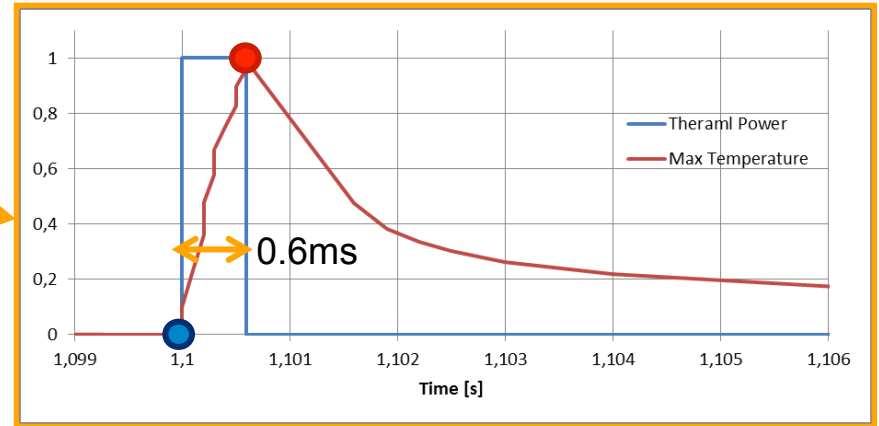
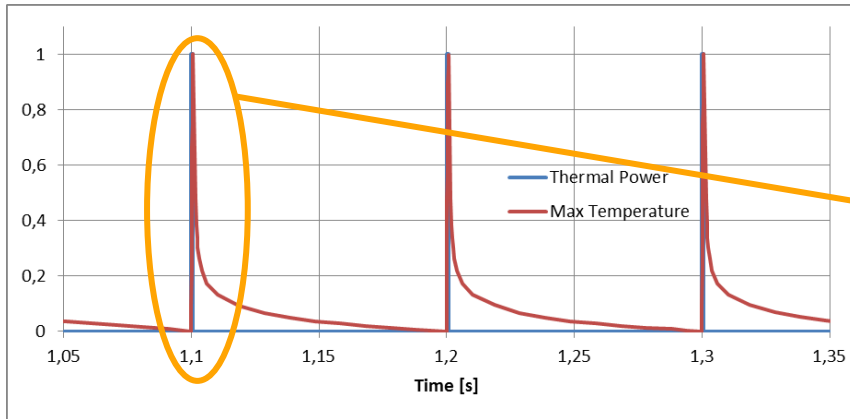


Thermal effect on offset mirror

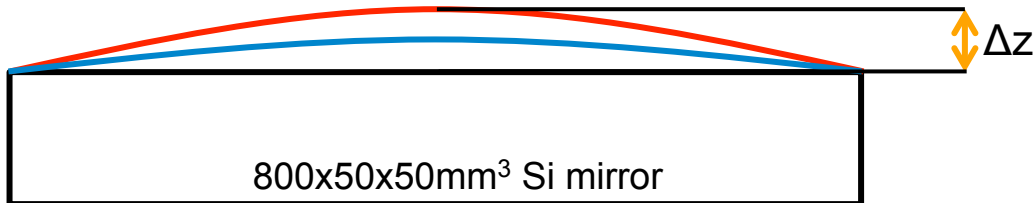


(Simulations by Daniele La Civita and Antje Trapp)

Max temperature variation ($\Delta T_{\max} = 0.3-0.6^\circ\text{C}$)

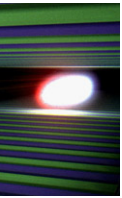


Dynamic thermal bump @ 10Hz

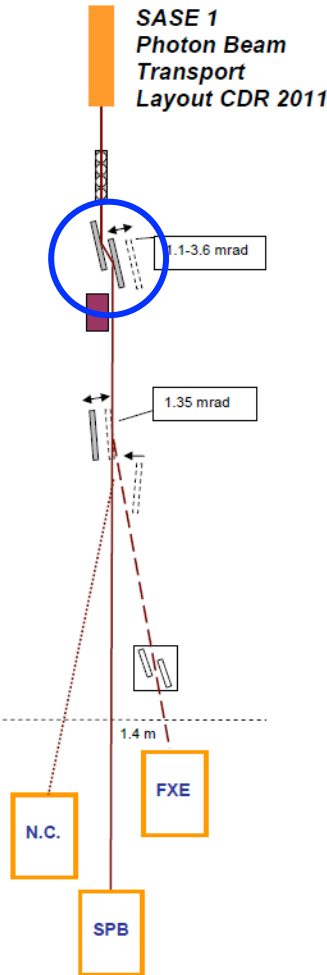


	Δz
Peak	18-33 nm
Average	15-29 nm

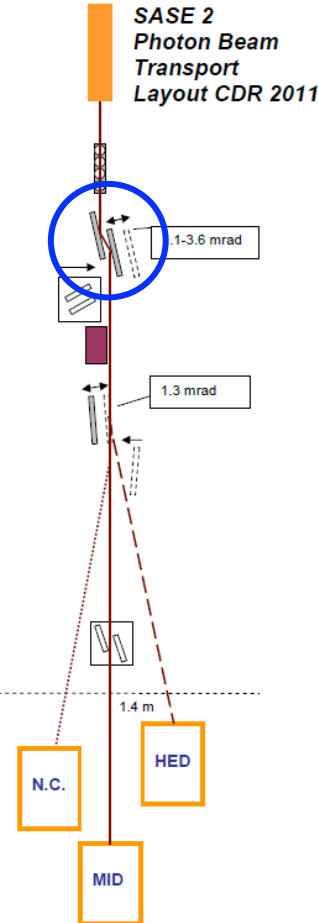
Bendable Mirrors in the Distribution System



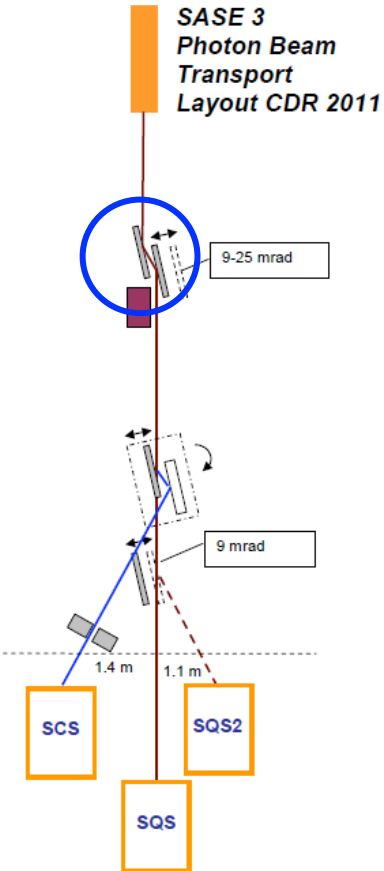
-205 m first undulator module
0 m source point FEL
15 m end of last module
230 m CRLs
270 m first offset mirror
280 m second offset mirror
300 m B.S collimator
322-354 m XS3
370 m distribution mirror left station
(380 m distribution mirror right station)
(430 m intermediate focus)
850 m Si monochromator (FXE)
900 m experimental area



-205 m first undulator module
0 m source point FEL
15 m end of last module
230 m CRLs
247-279 m XS2
290 m first offset mirror
300 m second offset mirror
(310 m option C-Mono, MID)
320 m B.S collimator
390 m distribution mirror left station
(395 m distribution mirror right station)
(460 m intermediate focus)
890 m Si monochromator (MID)
940 m experimental area

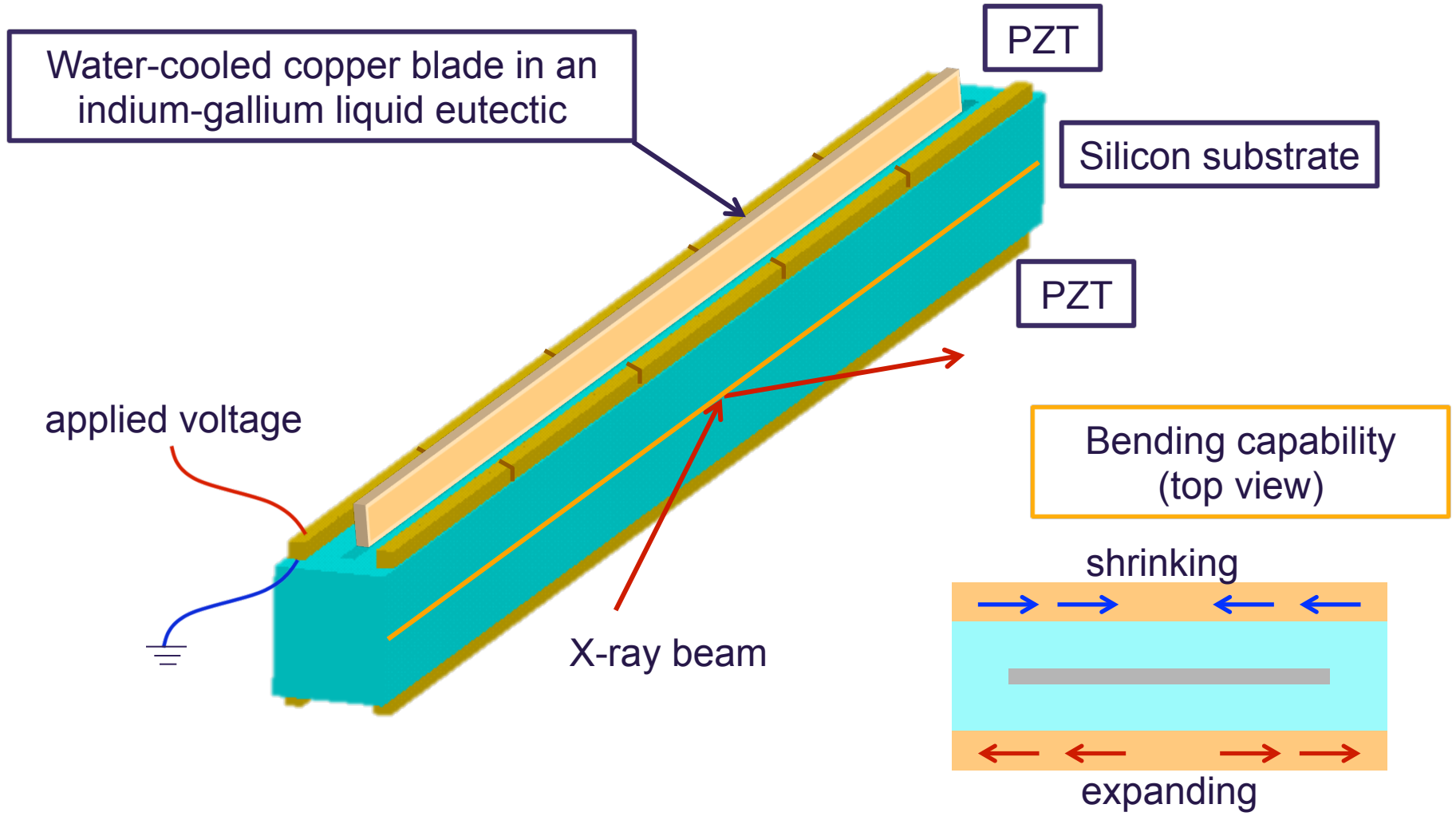
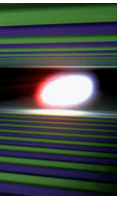


-116 m first undulator module
0 m source point
15 m end of last module
172-194 m XSDU2
250 m first offset mirror
252.8 m second offset mirror
260 m B.S collimator
353 m reflecting mirror
+ VLS grating 500 mm
357 m distribution mirror
412m horizontal slit
422 m experimental area

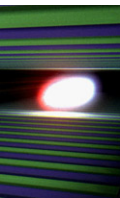


 = Bendable mirror

Bendable Mirror design

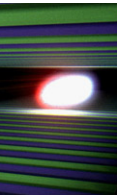


General Specification



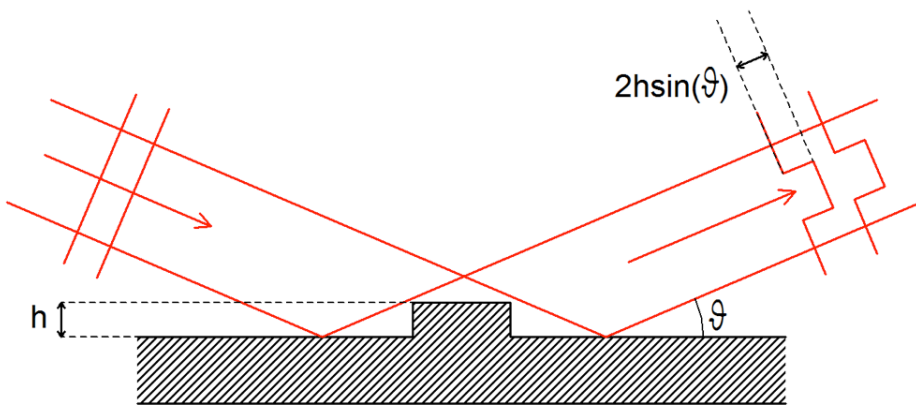
	Mirror specifications	Prototype specifications
Substrate length	930 mm	950 mm
Optical surf (mer x sag)	800x20mm ²	750x20mm ²
Substrate Material	Single crystal silicon	Single crystal silicon
Surface coating	B ₄ C	none
Figure	Flat	Flat
Cooling system	InGa eutectic bath	Groove present but not used

Height error (Peak to Valley) (4th order polynomial removed)	<2 nm	<20 nm
Slope error (root mean square)	<0.05 urad <0.5 urad sagittal	<1 urad <0.5 urad (3rd order removed) <5 urad sagittal
Roughness (@10x) rms	<0.3 nm	<0.3 nm
Radius of curvature	>600 km	>50 km >1 km sagittal
Bending capability	-50 km to flat to +50 km	-50 km to flat to +50 km



Wavefront preservation depends on:

- Mirror length → diffraction on mirror edges
- Residual height errors



$$\varphi = \frac{2h \sin \theta}{\lambda}$$

$$\varphi_{rms} \leq \frac{1}{14} \text{ Maréchal criteria}$$

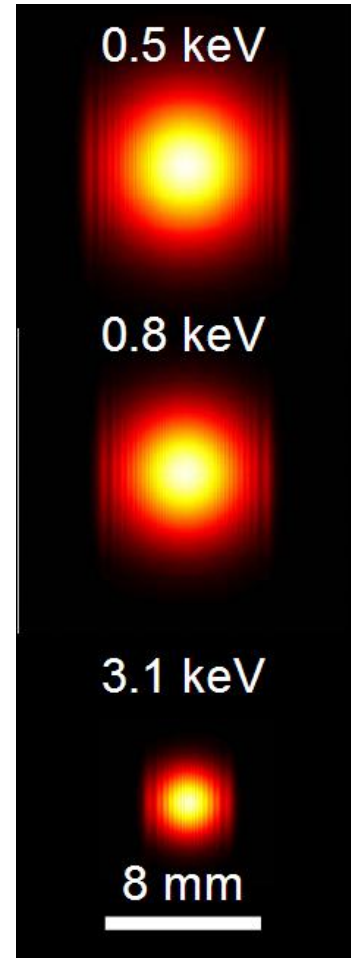
φ : phase error

θ : “grazing” incidence angle

λ : beam wavelength

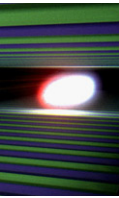
h : P-V error

$$h_{rms} < \frac{1}{28} \frac{\lambda}{\sin \theta} \approx \frac{1}{28} \frac{\lambda}{\theta}$$



Sinn, Samoylova, et al., “X-ray Optics and Beam Transport CDR”, April 2011 and F. Siewert et al., Optics Express **20**, 4525, (2012)

General Specifications



■ Why so long ?

To allow 4-sigma cutting and operation in different conditions/energies/footprint

To minimize thermal load over the surface

■ Why so “flat” ?

To reduce wavefront aberrations (fully coherent beam!)

■ Why bendable ?

To correct for the different beamlines length. To correct offset mirrors thermal load.

To correct low spatial frequency aberrations on the surface

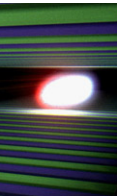
■ Why InGa cooled ?

To allow mirror cooling without clamping (=bending)

■ Why B4C coated ?

To protect the mirror from beam damage (eventual misalignment and misfocusing)

Prototype manufacturing



Substrate preparation +
Standard polishing

Ion Beam polishing
+ Internal Metrology

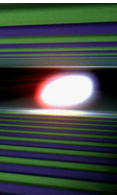
Metrology at BESSY
(HZB)

Today

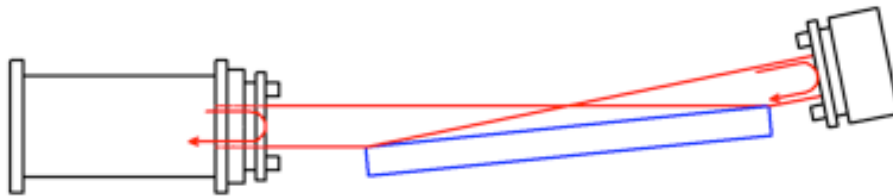
Advanced polishing (EEM)
+ Internal Metrology

Final Metrology at
BESSY (HZB)

Internal Metrology (THALES-SESO)



Two different methods using Fizeau interferometry:



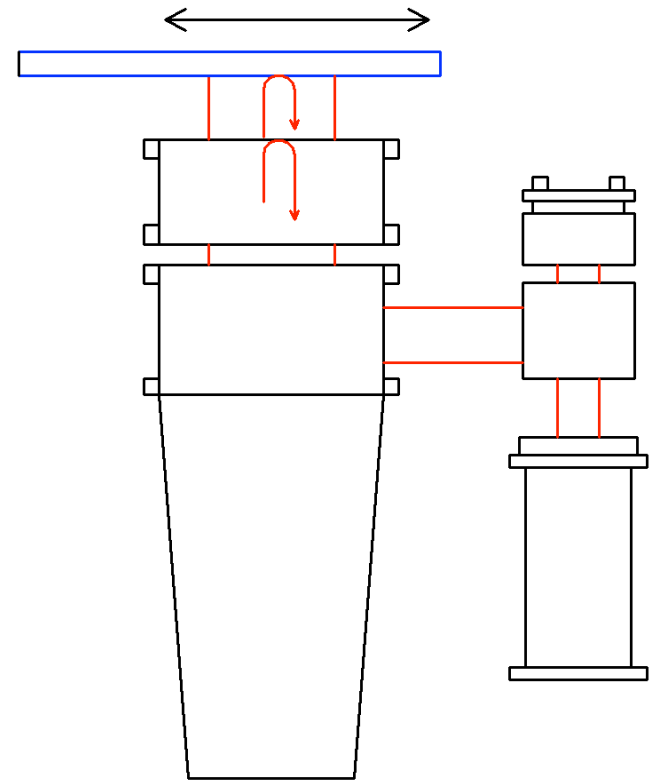
Grazing Incidence Setup

Pros:

- Direct height profile measurement
- Full Map measurement
- High spatial resolution
- Fast (=seconds)

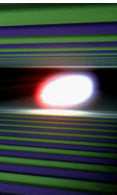
Cons:

- Limited by Reference Flat Calibration

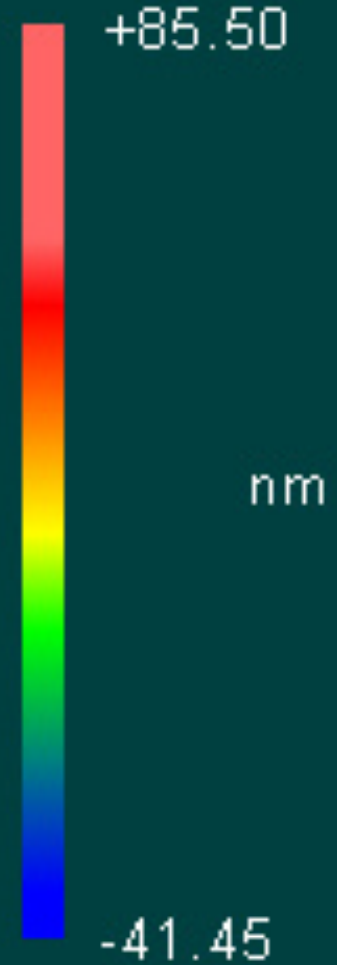
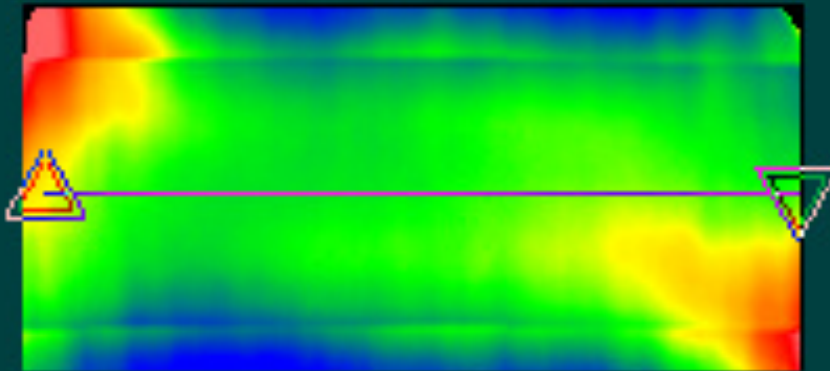


Normal Incidence/Stitching Setup

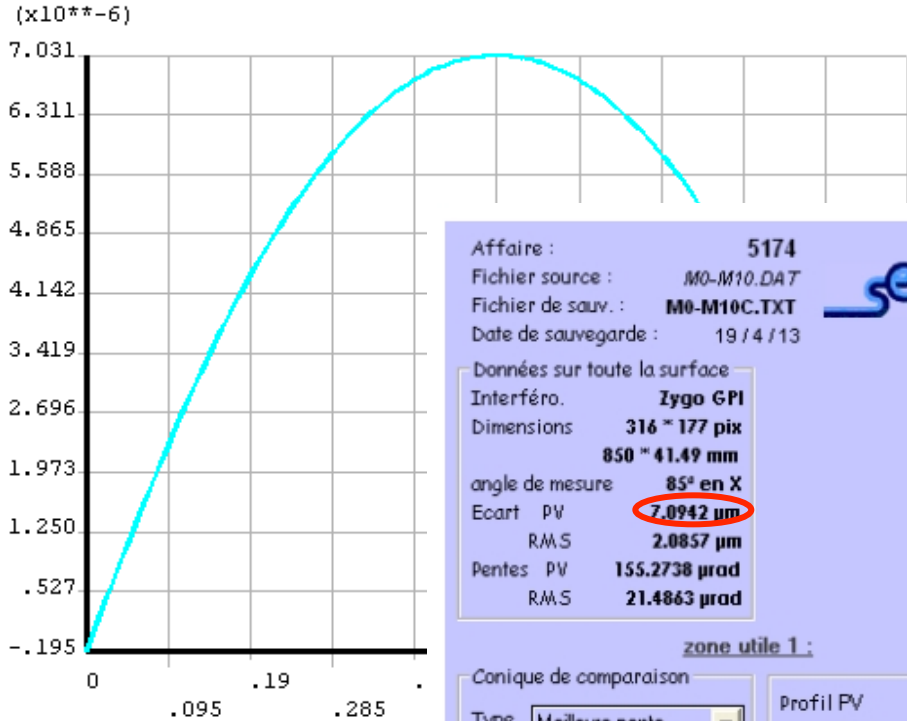
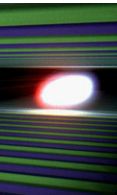
Full surface measurement (THALES-SESU)



Courtesy of Luca Peverini (THALES-SESU)



Simulations V.S. Measurements



Simulations by
Fan Yang

Affaire : **5174**
 Fichier source : *M0-M10.DAT*
 Fichier de sauv. : **M0-M10C.TXT**
 Date de sauvegarde : 19 / 4 / 13

Données sur toute la surface
 Interféro. **Iygo GPI**
 Dimensions **316 * 177 pix**
850 * 41.49 mm
 angle de mesure **85° en X**
 Ecart PV **7.0942 μm**
 RMS **2.0857 μm**
 Pentes PV **155.2738 μrad**
 RMS **21.4863 μrad**

zone utile 1 :
 Conique de comparaison
 Type **Meilleure pente**
 Coefficient **0**
 Rayon (km) **-12.997184**
 Calculer

Profil PV **.0789 μm**
 RMS **.0237 μm**
 Pente PV **2.2939 μrad**
 RMS **.3515 μrad**

zone utile 2 :
 Conique de comparaison
 Type **Aucune**
 Coefficient
 Rayon (km)
 Calculer

Profil PV
 RMS
 Pente PV
 RMS

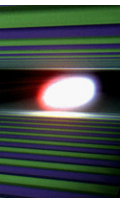
Nb de points : **55932**
 Ecart PV : **7.0942 μm**
 RMS : **2.0857 μm**
 Pente PV : **155.2738 μrad**
 RMS : **21.4863 μrad**
 X : **304**
 Y : **222** (μm)
 Moy. de 8 Profils
 supprimer

profil horizontal en micrometre

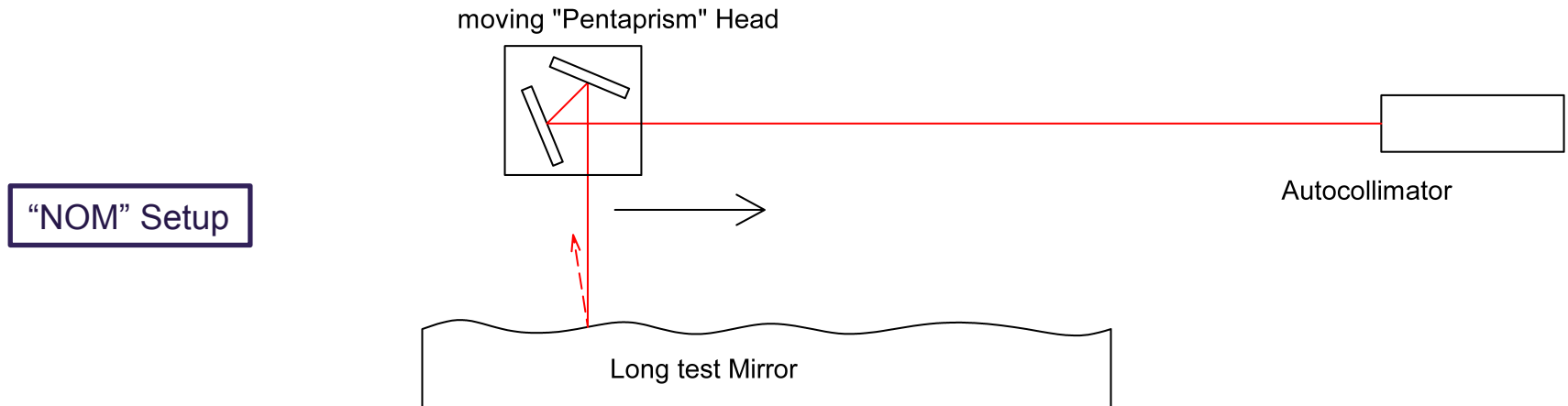
lissage **3**
 ligne **88**
 Recalculer

Zone utile
 ZU 1 : **850 mm**
 ZU 2 : **mm**

pentcs en microradian



Deflectometric method:



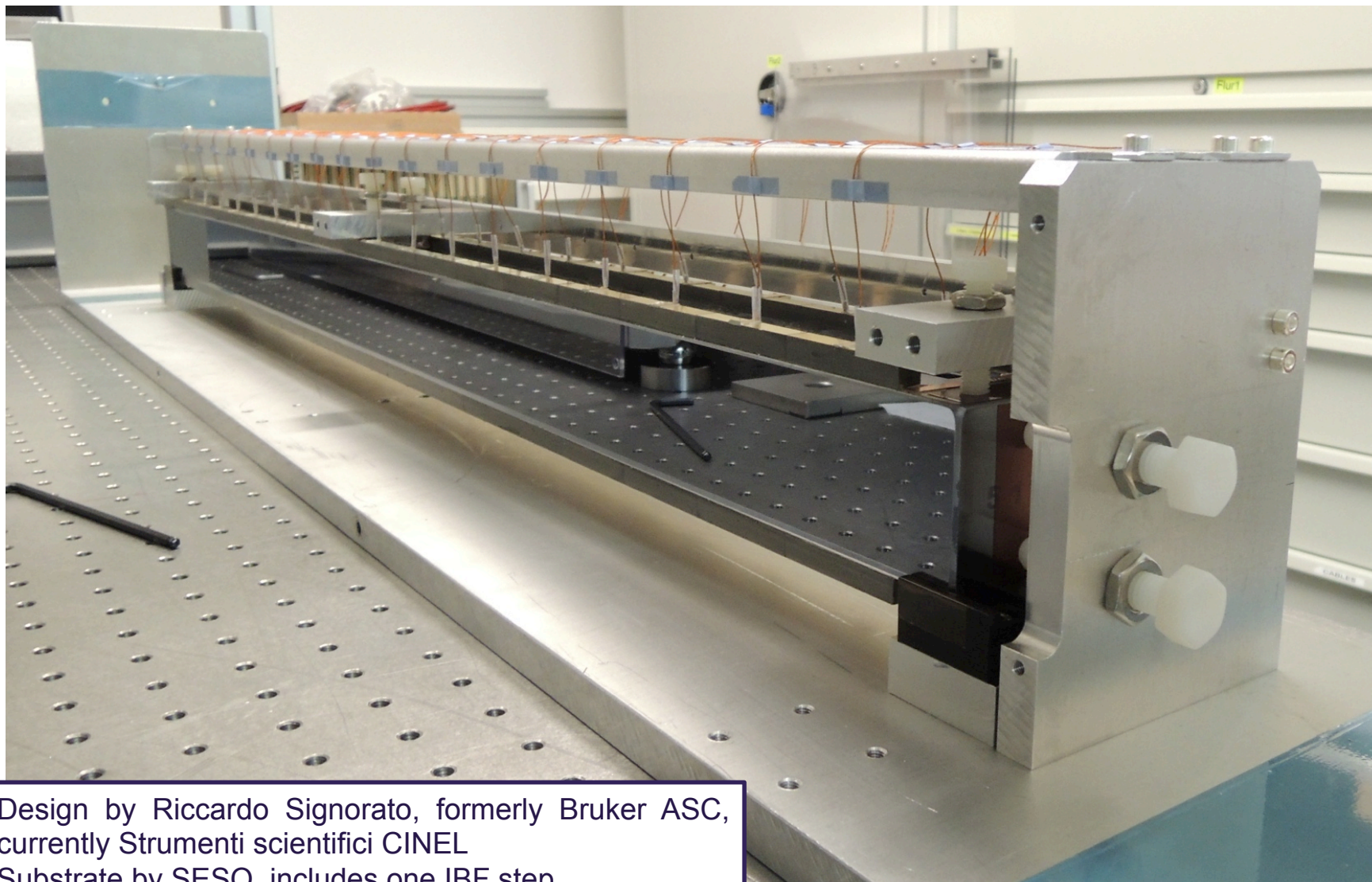
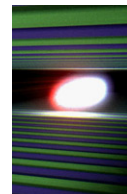
Pros:

- No reference needed
- System already calibrated

Cons:

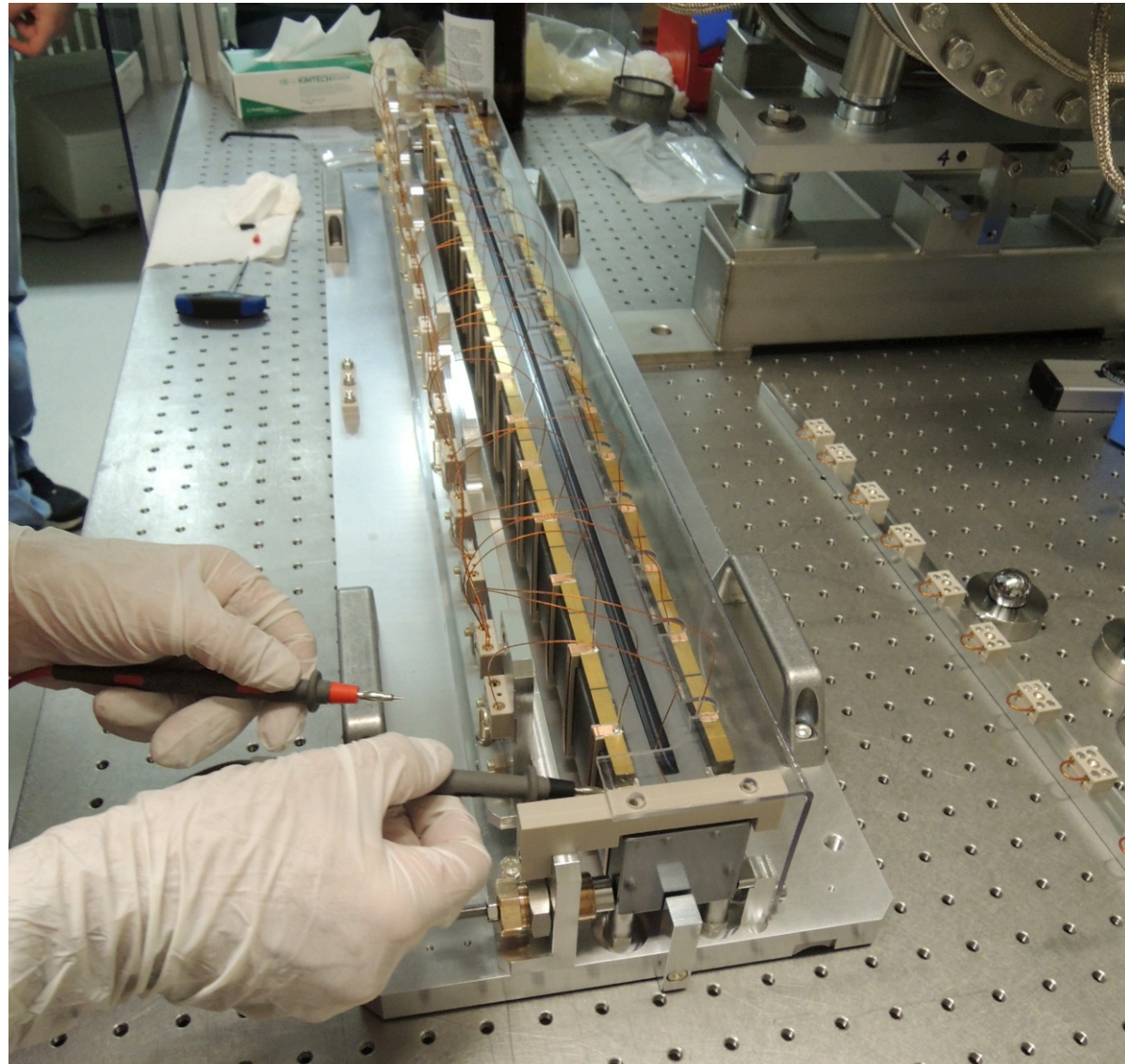
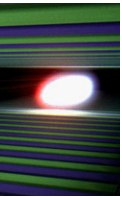
- Slope measurement (=indirect height profile measurement)
- "Slow" (=minutes)
- Limited to a profile in its basic implementation (but with BESSY-NOM, slope mapping is possible)

Prototype built by Bruker/CINEL/SESO



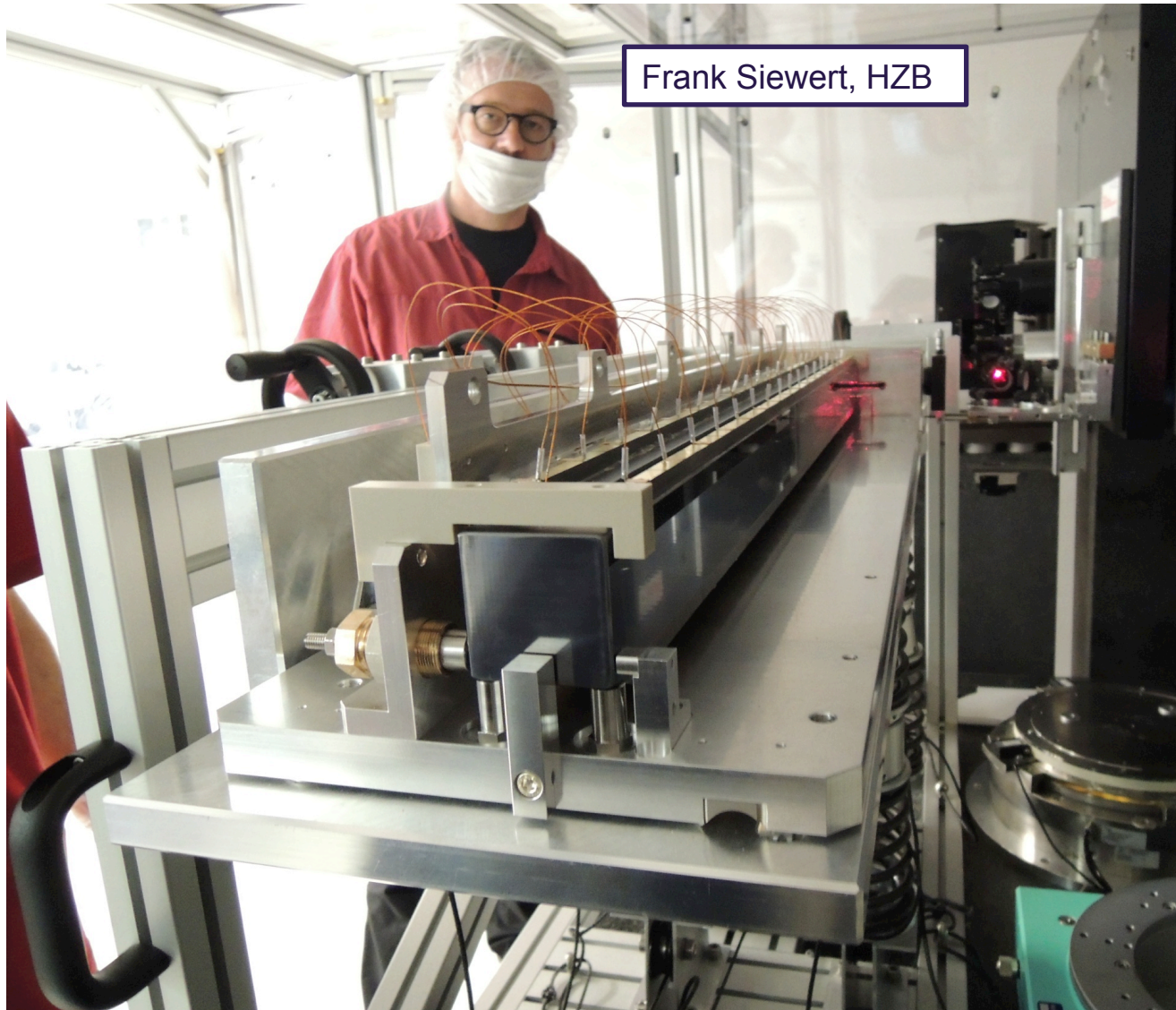
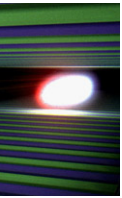
Design by Riccardo Signorato, formerly Bruker ASC,
currently Strumenti scientifici CINEL
Substrate by SESO, includes one IBF step

Prototype built by Bruker/CINEL/SES0



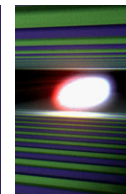
Hands of Riccardo Signorato

Measurements with NOM, BESSY

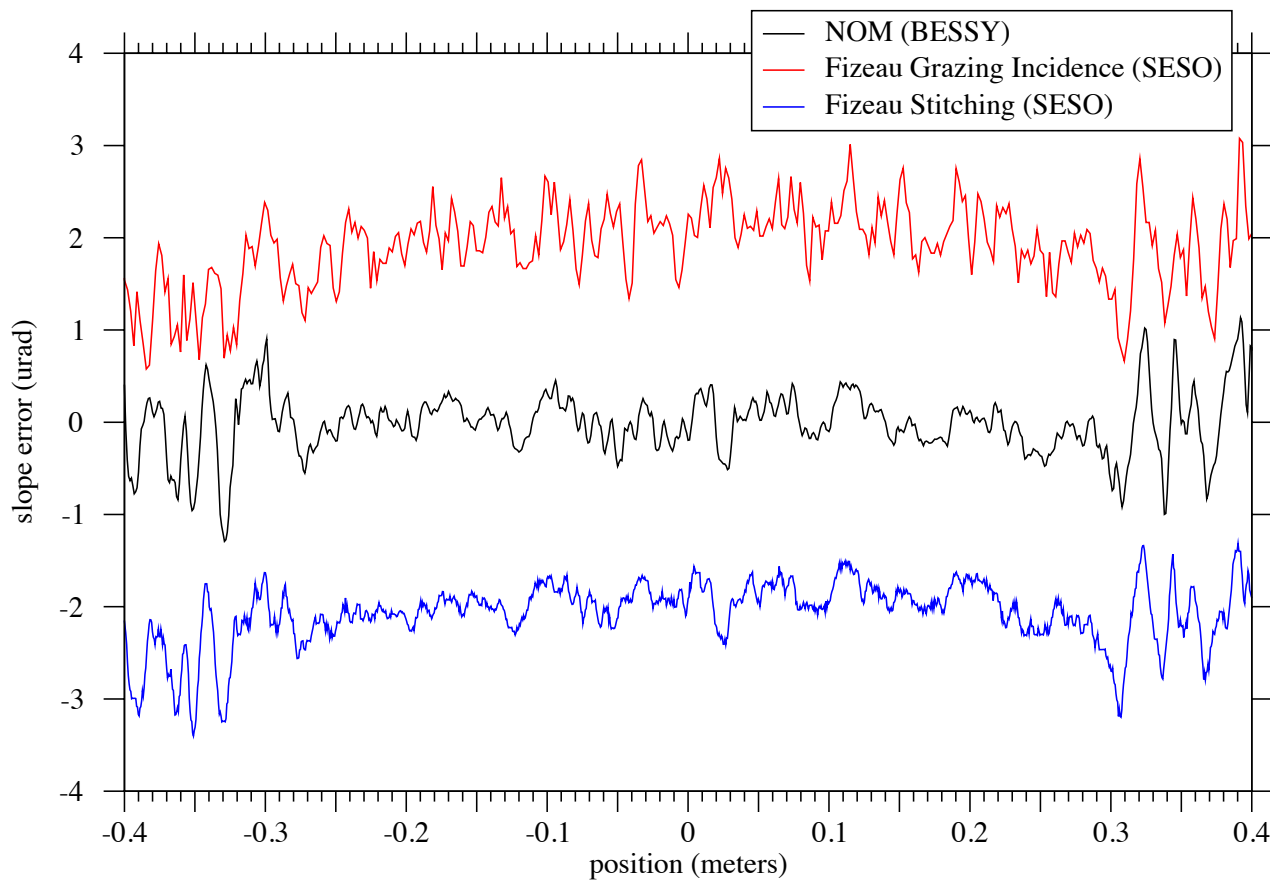


Frank Siewert, HZB

Metrology results



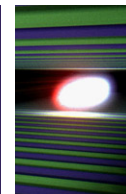
Residual slope error



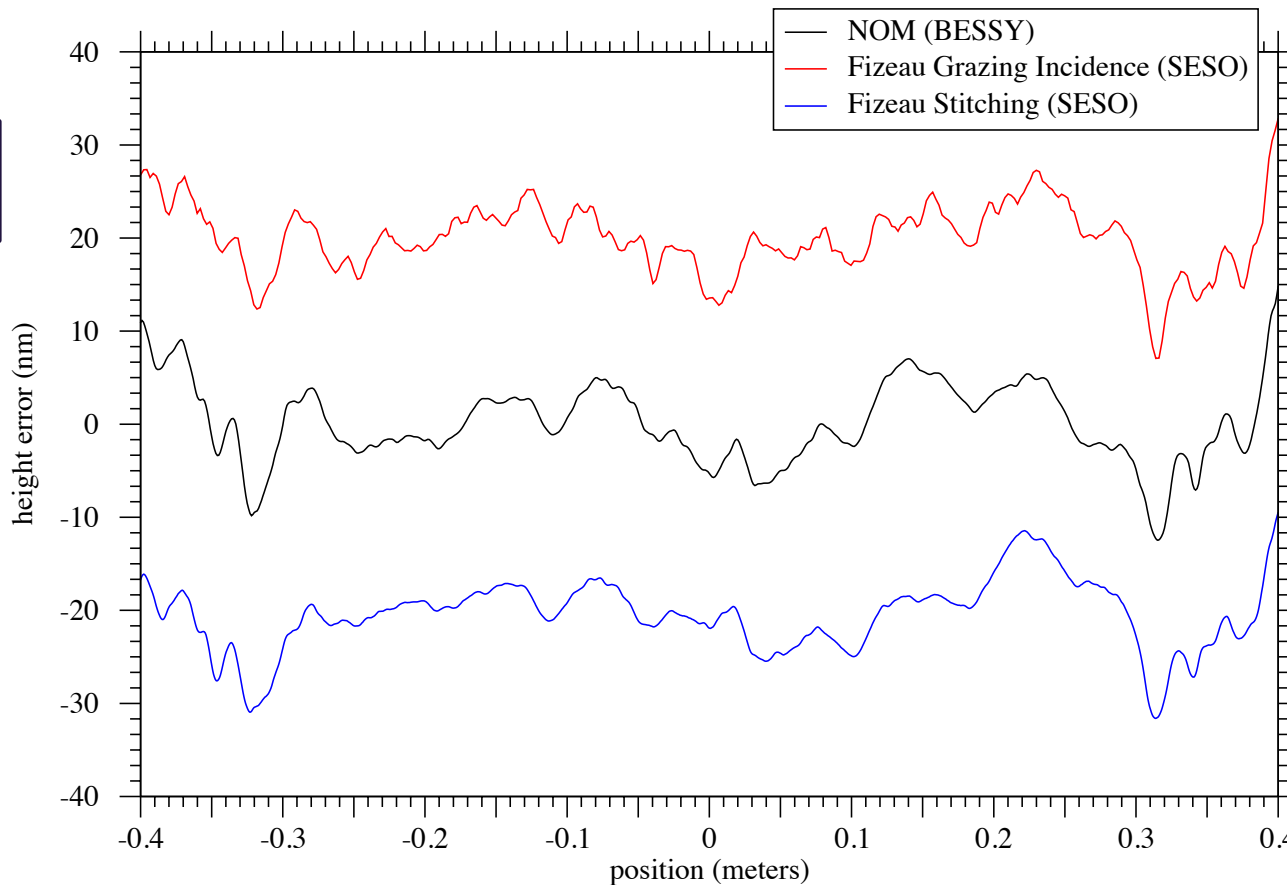
RMS residual slope error:

- NOM (BESSY): 0.317 urad
- SESO (Grazing Incidence): 0.345 urad
- SESO (Stitching): 0.319 urad

Metrology results



Height error profile
(3rd order correction)



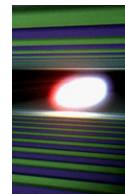
RMS height error (3rd order correction):

- NOM (BESSY): 3.8 nm
- SESO (Grazing Incidence): 3.2 nm
- SESO (Stitching): 3.6 nm

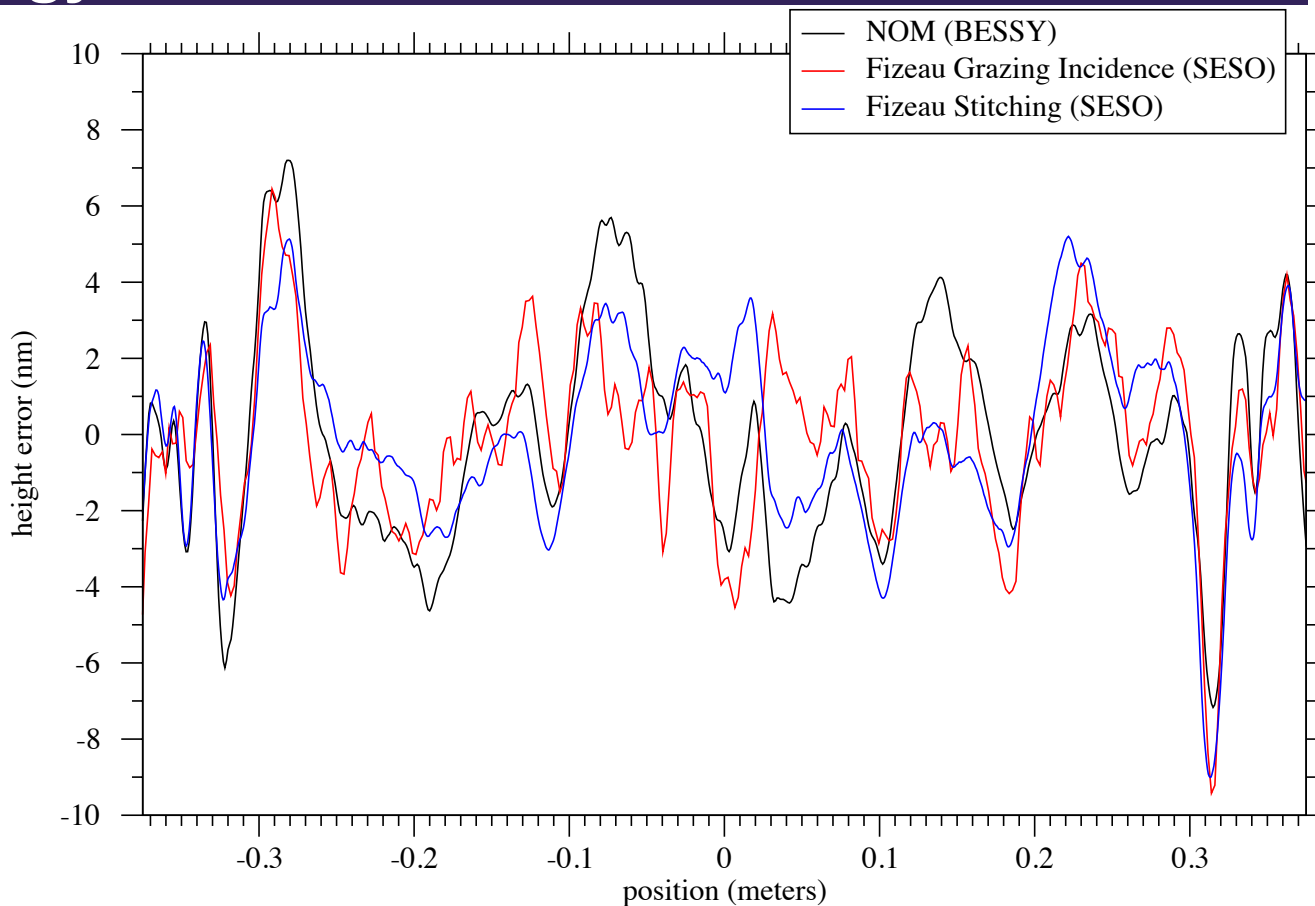
P-V height error (3rd order correction):

- NOM (BESSY): 18.7 nm
- SESO (Grazing Incidence): 18.0 nm
- SESO (Stitching): 18.8 nm

Metrology results



Height error profile
(6rd order correction)



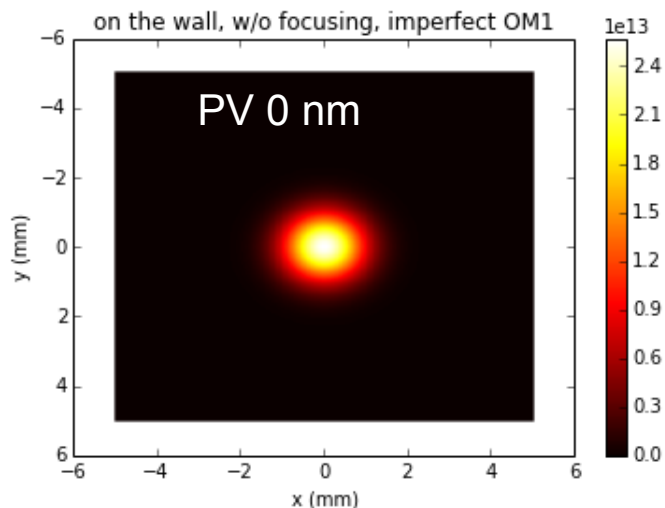
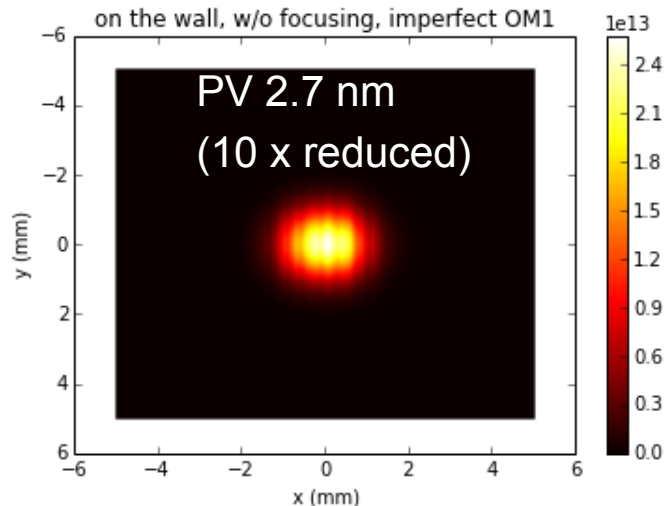
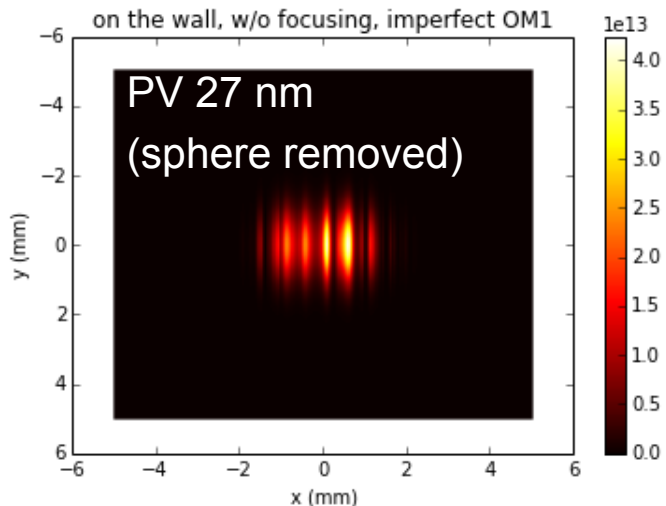
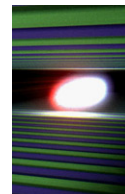
RMS height error (6rd order correction):

- NOM (BESSY): 2.8 nm
- SESO (Grazing Incidence): 2.3 nm
- SESO (Stitching): 2.4 nm

P-V height error (6rd order correction):

- NOM (BESSY): 14.4 nm
- SESO (Grazing Incidence): 15.9 nm
- SESO (Stitching): 14.2 nm

How would the prototype perform at E.XFEL?

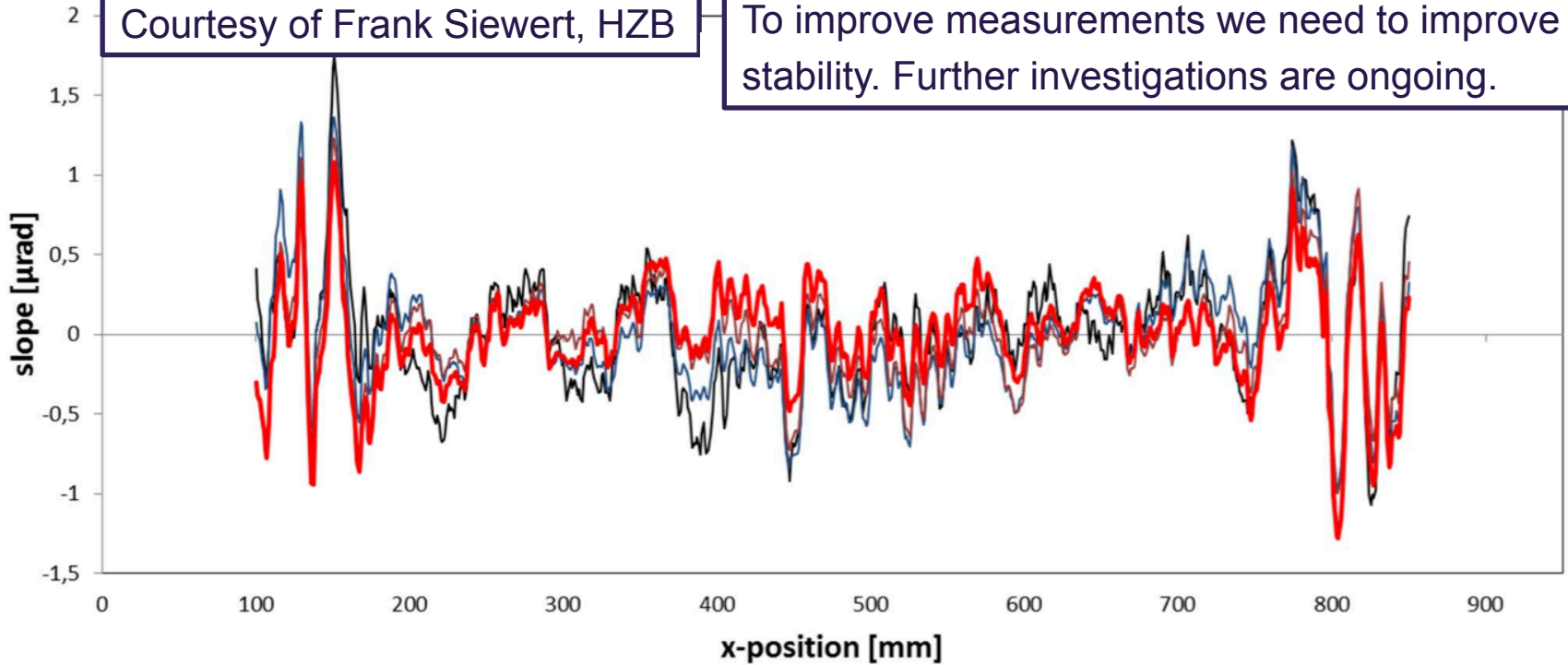
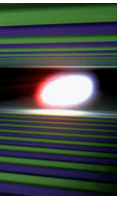


Calculations
by
Liubov
Samoylova,
Maurizio
Vannoni

SASE1 beamline,
simulated with:

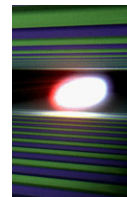
12.4 KeV (= λ 0.1 nm),
distance 625 m,
grazing angle 2 millirad,
e-bunch charge 0.1 nC

Stability issues

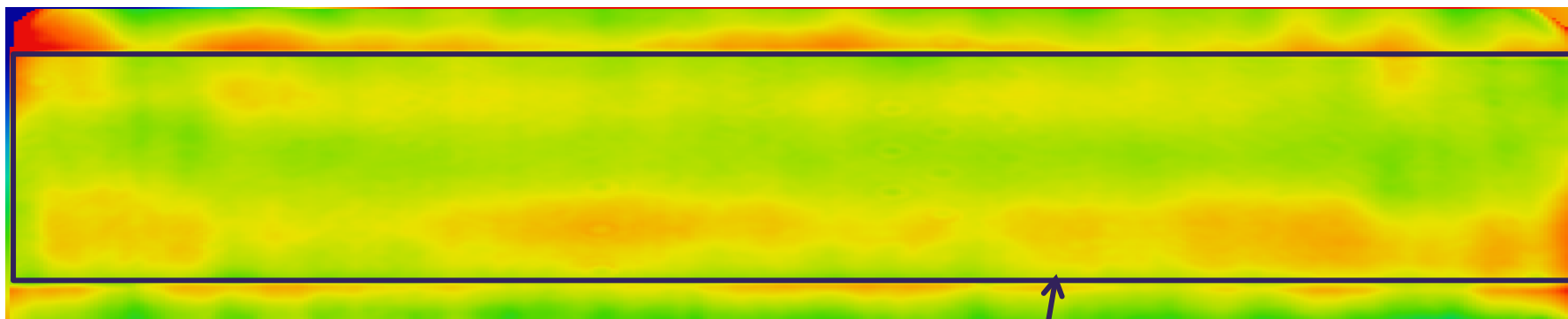


Residual slope: 0.31 μrad rms on 750 mm length

Radius of curvature: -650 km (convex)

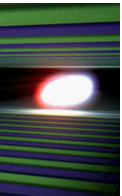


Height map



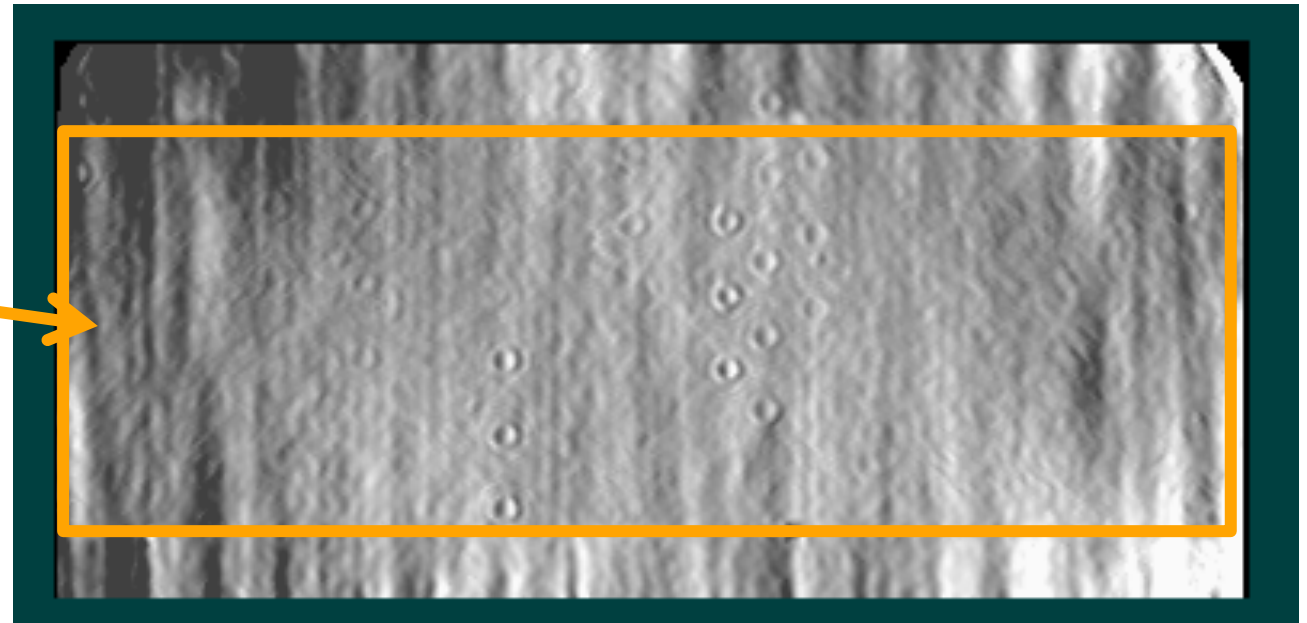
Ion Beam polished area

Full surface measurements (THALES-SESU)

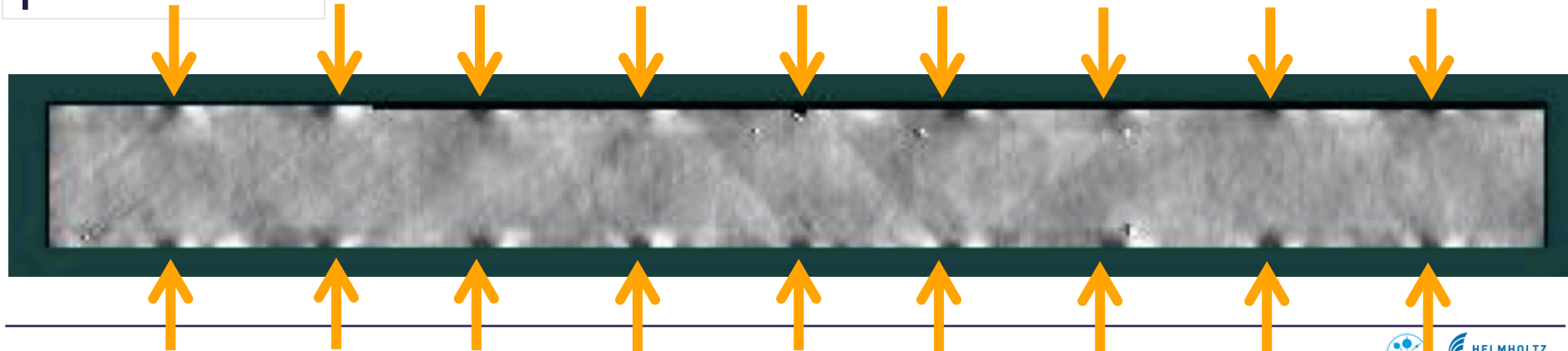


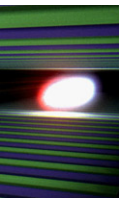
Slope map

Ion Beam
polished
area

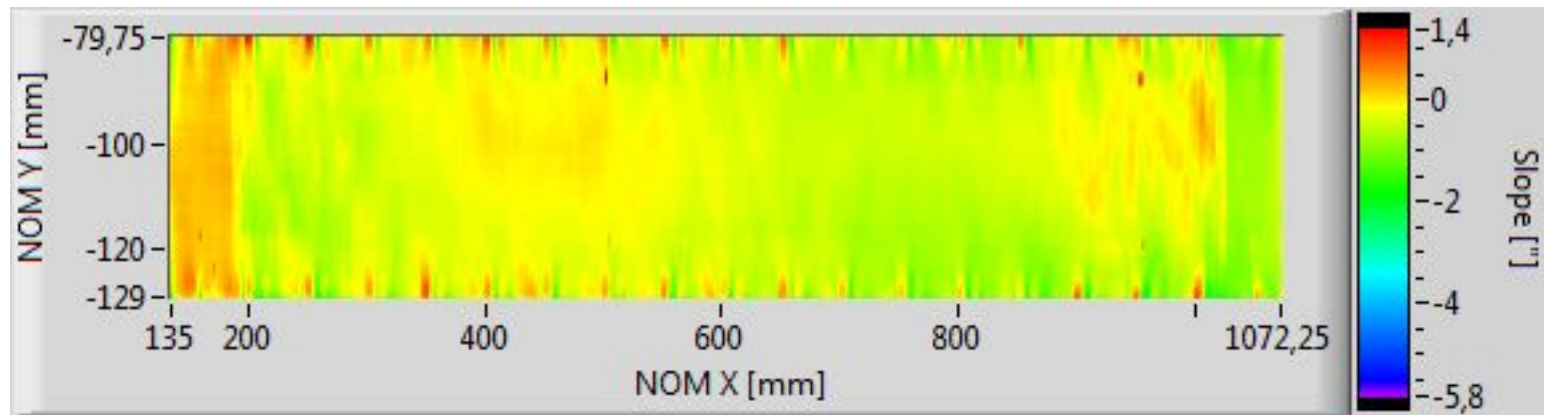


piezo

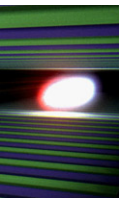




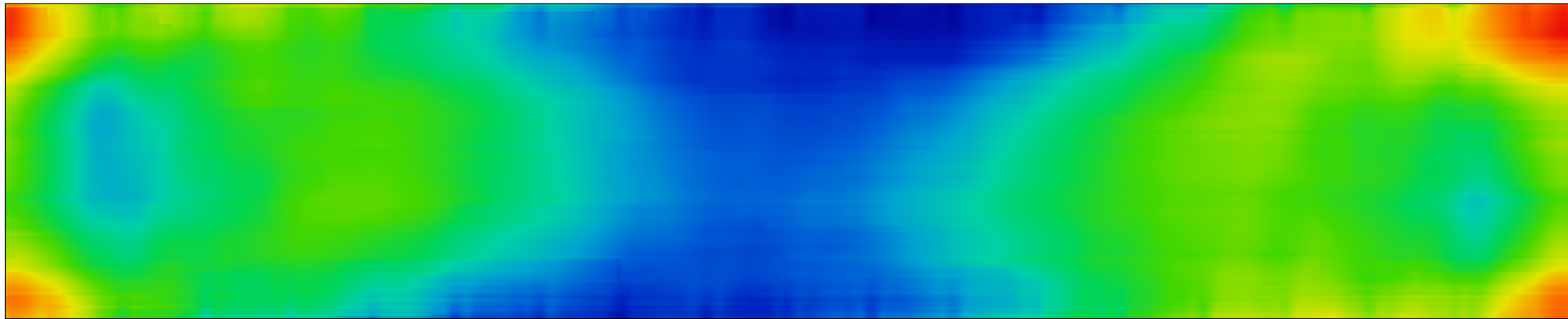
Slope map



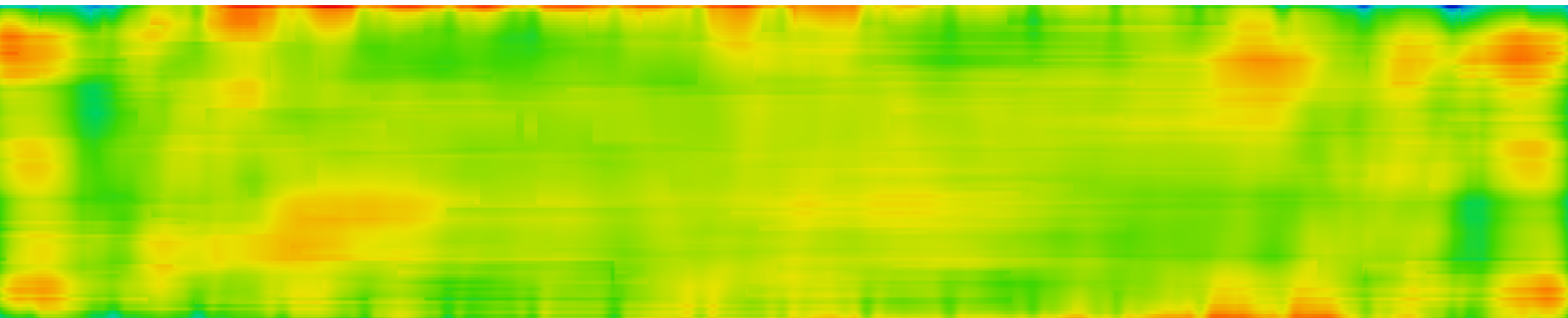
Full surface measurement (HZB)

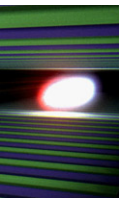


Height map – face up

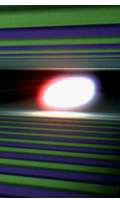


Height map – face up – polynomial subtracted





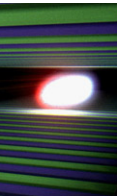
- Present state:
 - The prototype is ok with specifications
 - The metrology is stretched to the limit but still reliable.
 - Combining height and slope measurements we retrieve additional information
- Further details to investigate
 - Piezo characterization, EEM polishing (JTEC), B4C coating, InGa cooling...



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